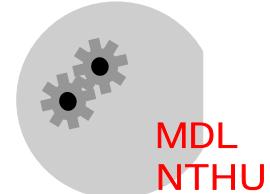


Outline

- 1 Introduction**
- 2 Basic IC fabrication processes**
- 3 Fabrication techniques for MEMS**
- 4 Applications**
- 5 Mechanics issues on MEMS**



3. Fabrication Techniques for MEMS

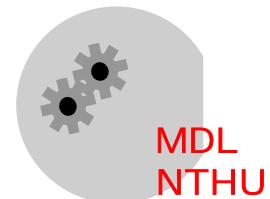
3.1 Bulk micromachining

3.2 Surface micromachining

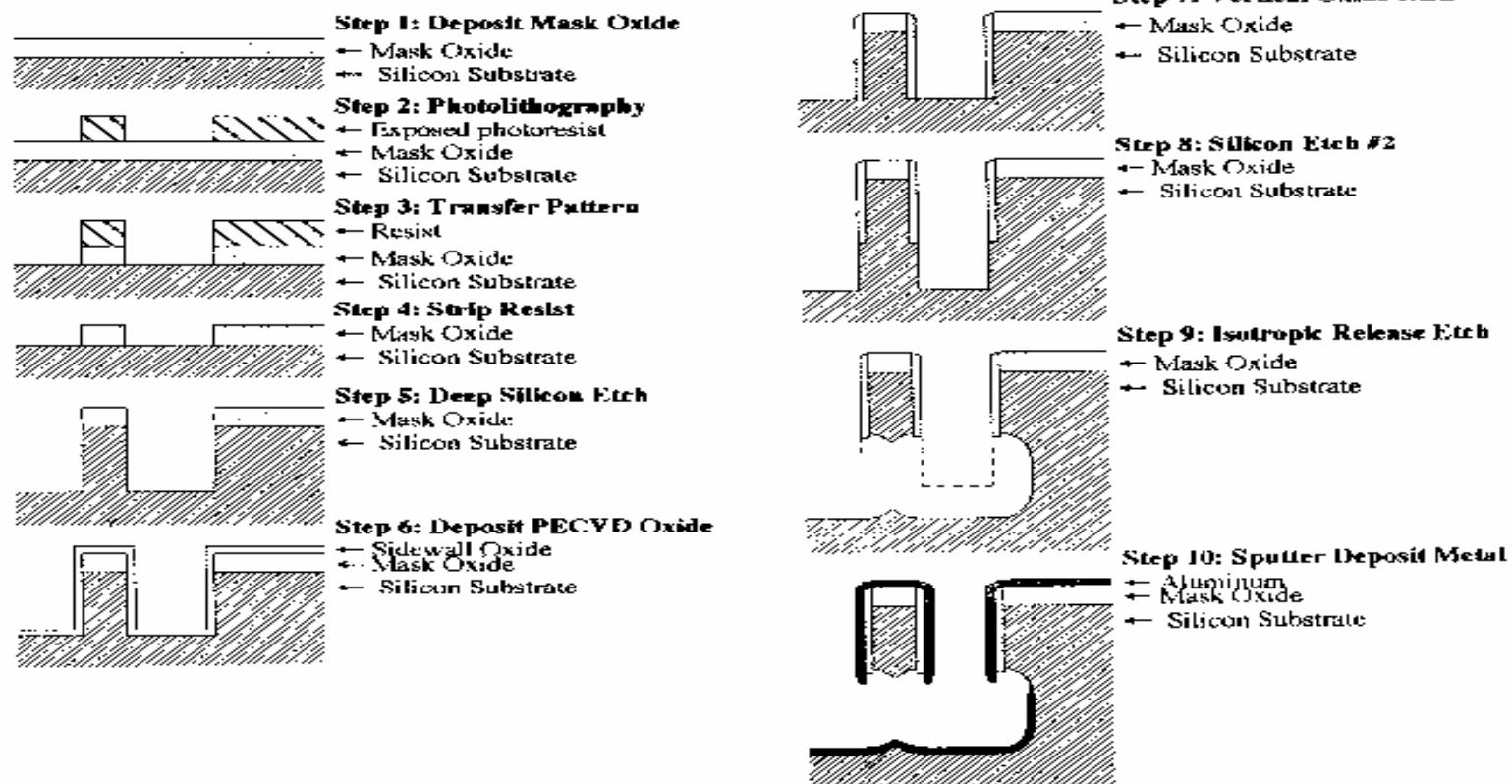
3.3 LIGA process

3.4 Hybrid micromachining

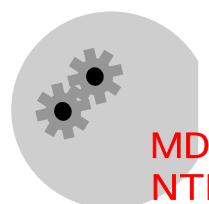
3.5 Thick micromachined structures



SCREAM process



N.C. MacDonald, Transducer'91, 1991



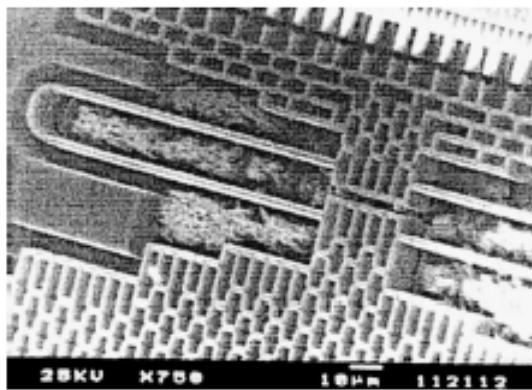


Fig. 7. SEM photo of one tether with stop structure.

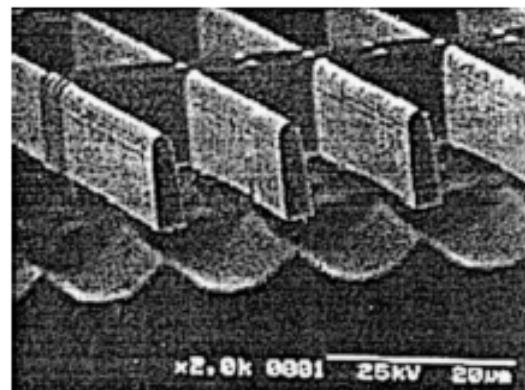
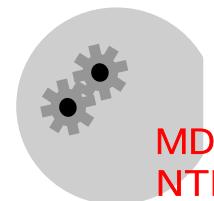
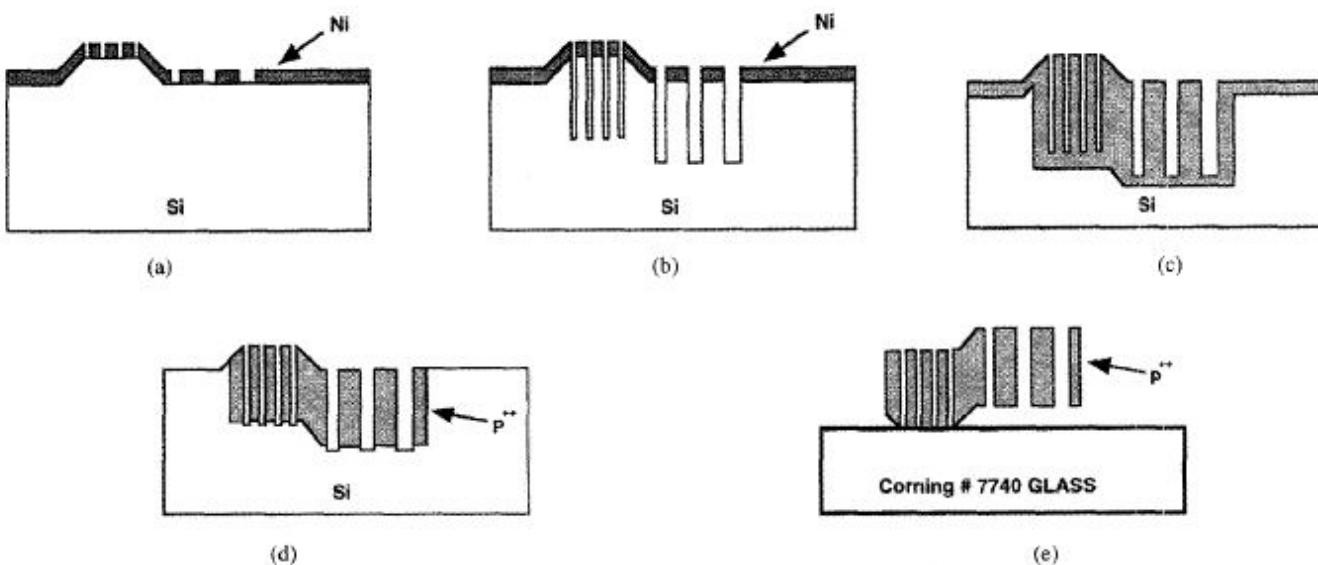


Fig. 8. SEM photo of cross-section of released non-parallel plates.

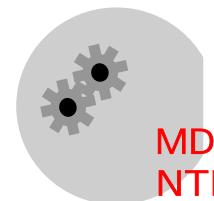
F.E.H. Tay, Sensors and Actuators A, 2000

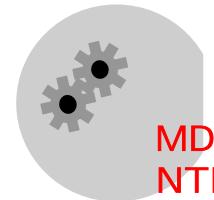
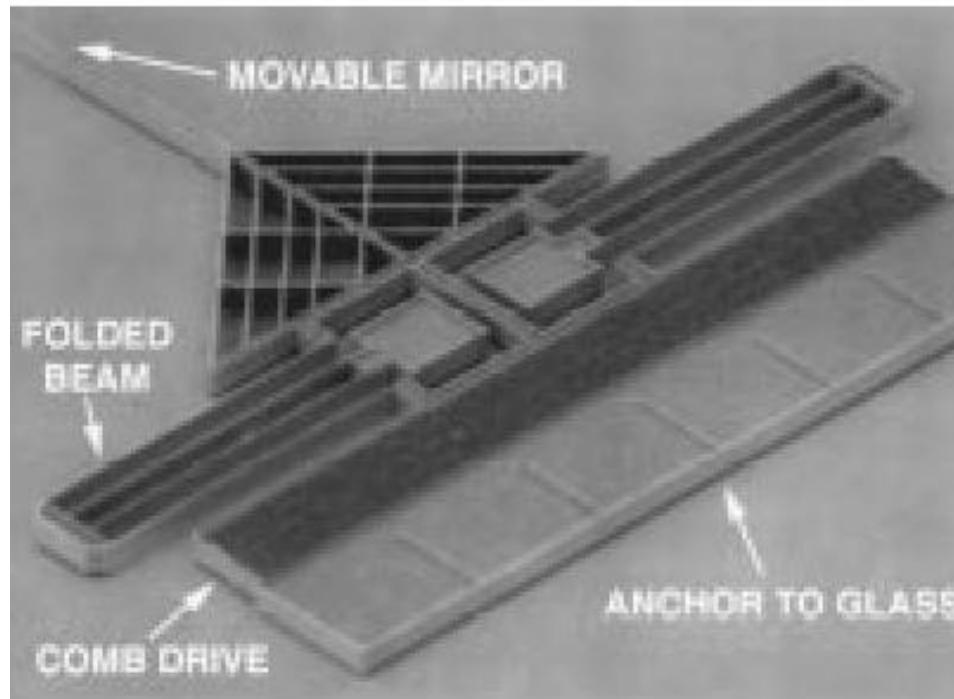


DWP, dissolved wafer process

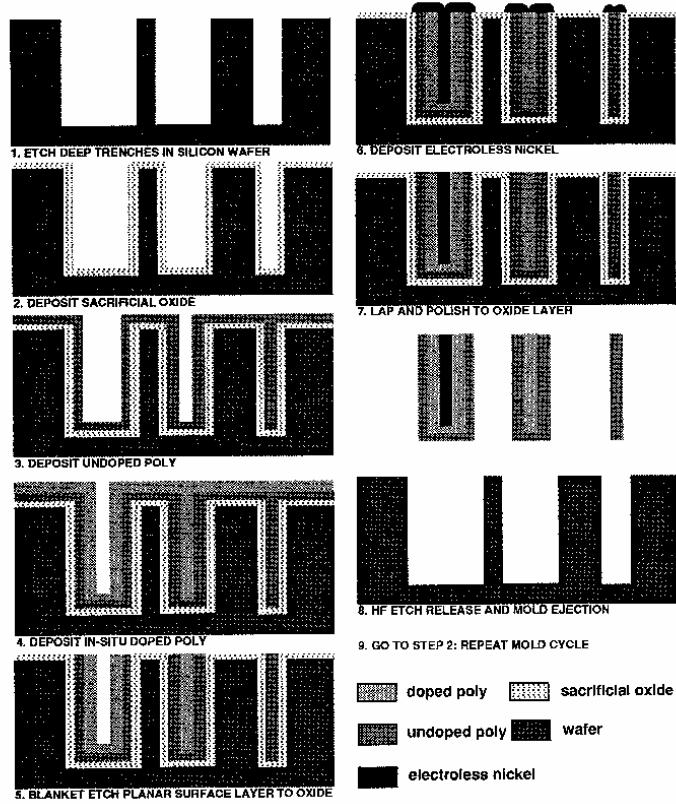


S. Pang, U. of Michigan, 1992





HexSil



1. Microstructure before release



2. Deposit & pattern metal pads

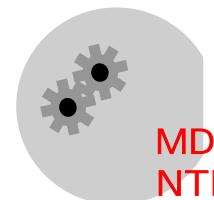


3. Release microstructures by etching oxide



4. Align, bond & transfer by pulling away and breaking tethers

R. Howe, UC Berkeley, 1995



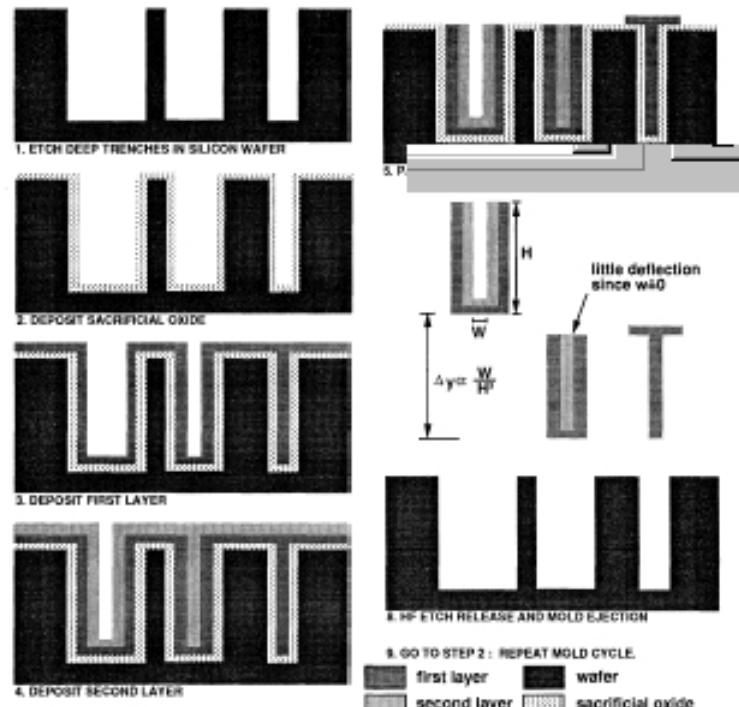


FIGURE 4. Trench molded bimorph beams

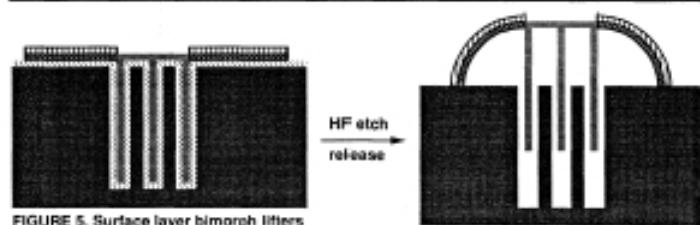
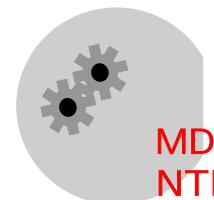
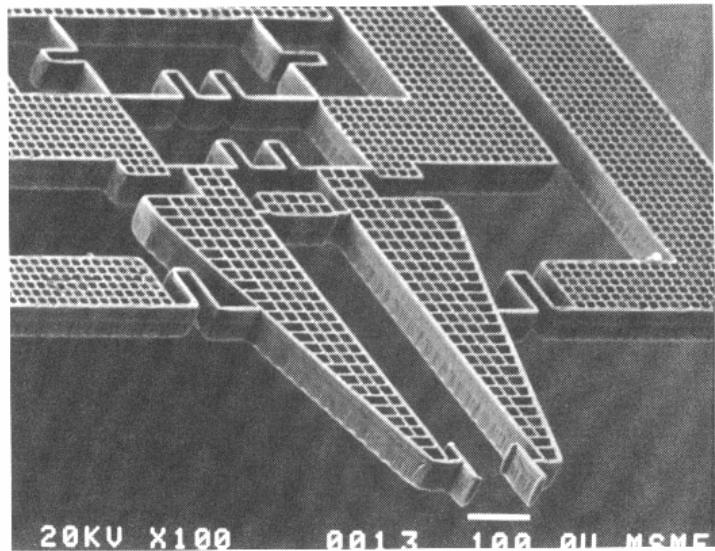


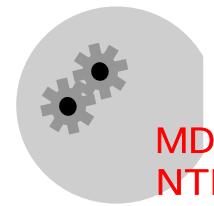
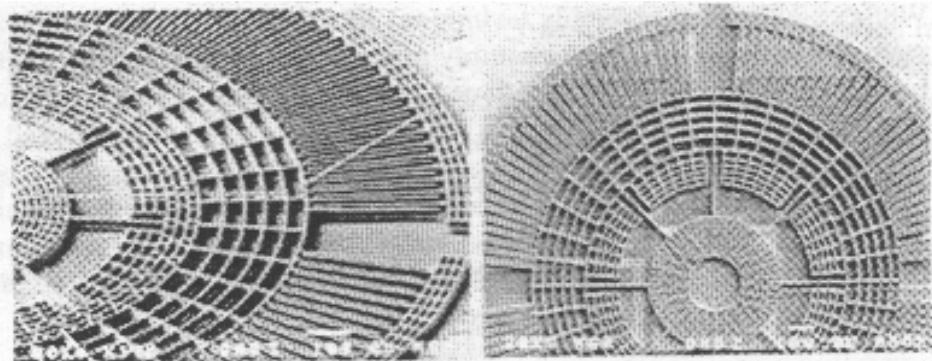
FIGURE 5. Surface layer bimorph filters



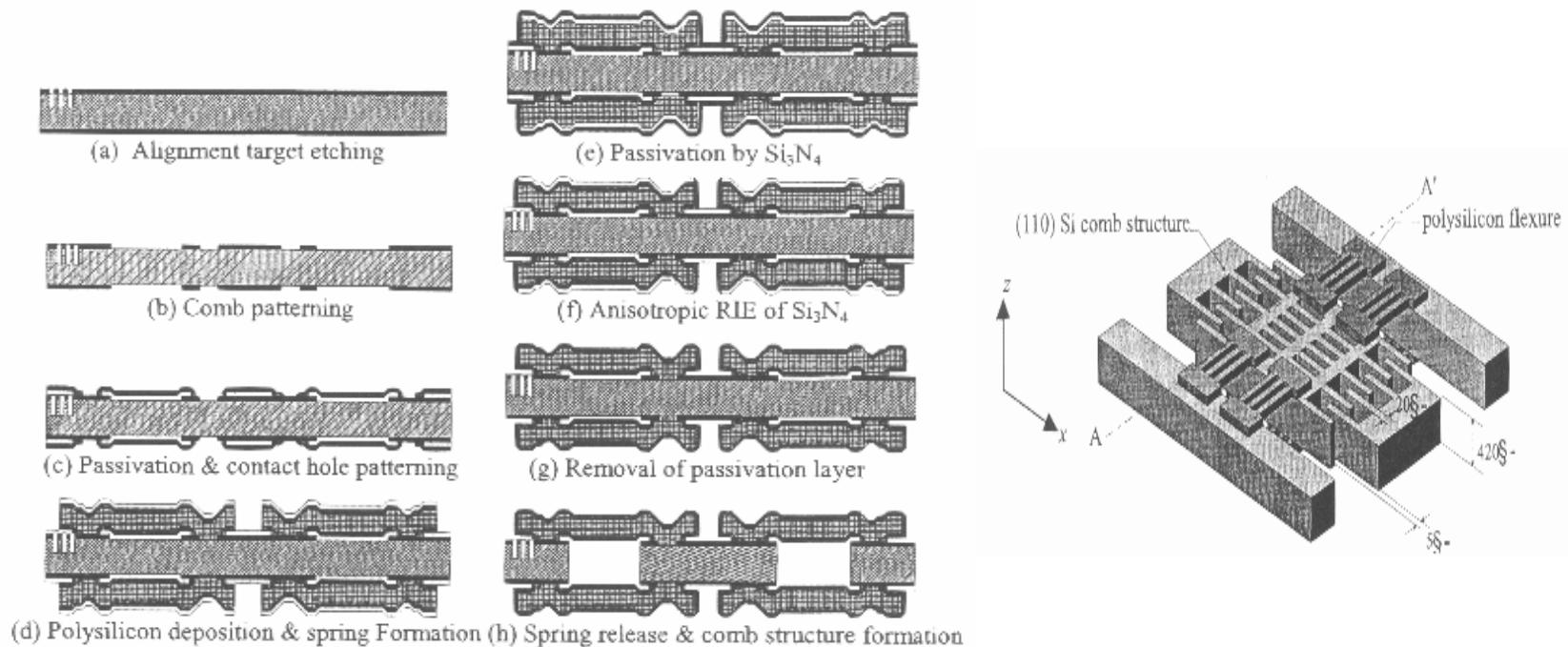
- HexSil tweezers



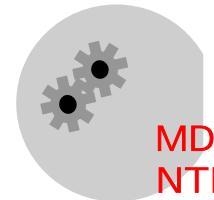
- HexSil comb drive



(110) silicon wafer process

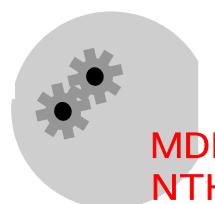
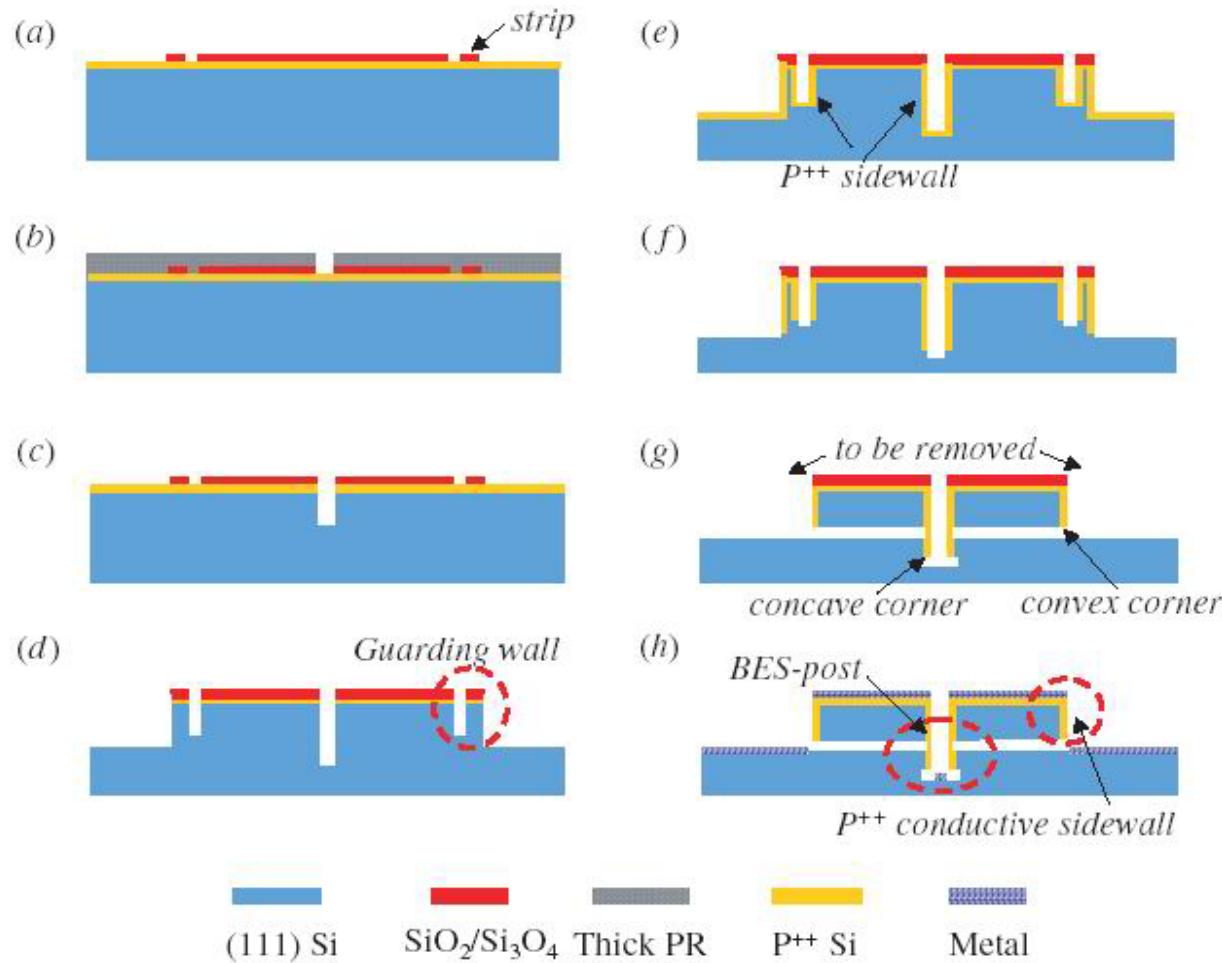


Seoul National University, 1998



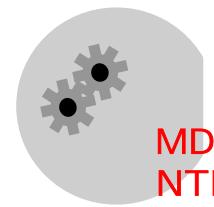
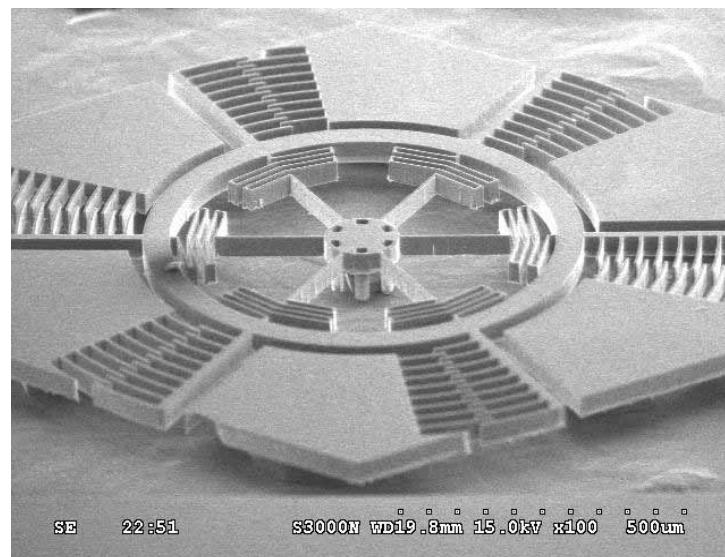
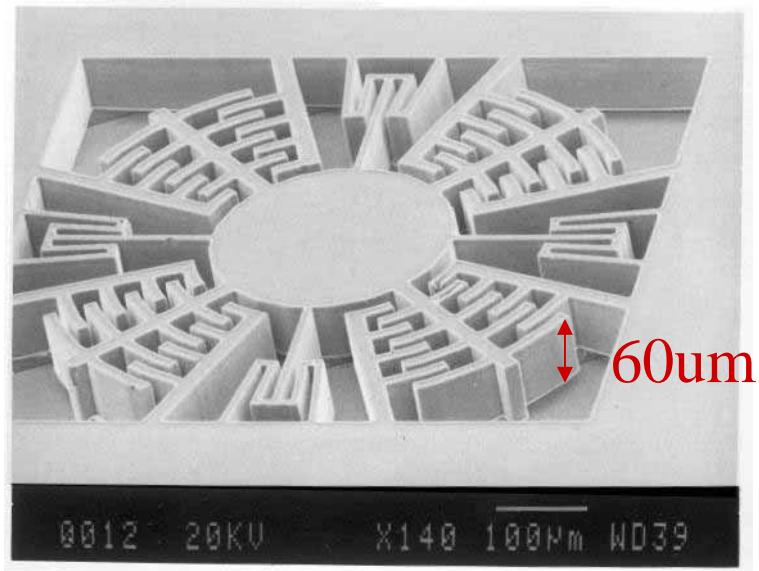
MDL
NTHU

BELST -- (111) silicon wafer process

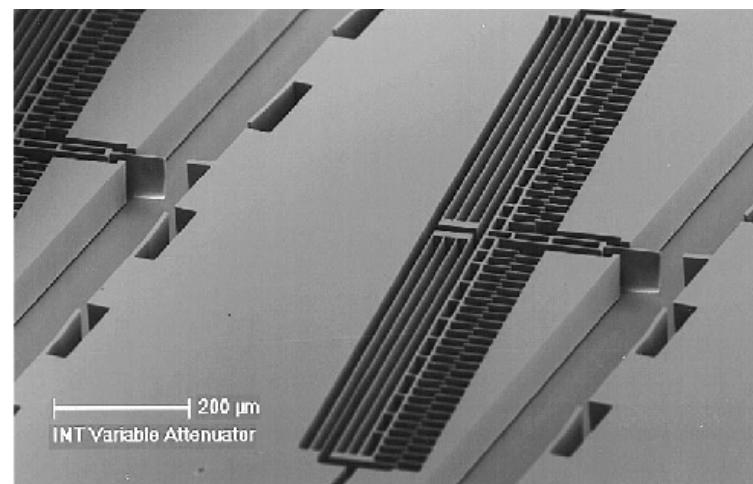
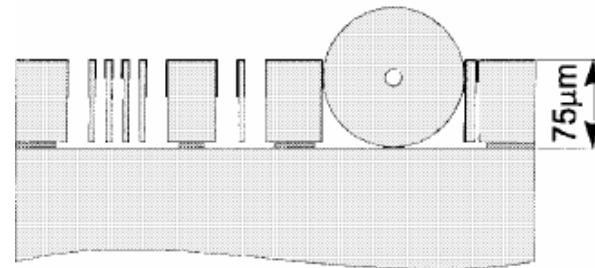
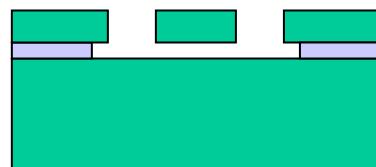
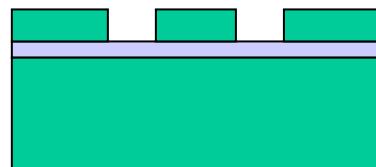


MDL
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Micro scanner



SOI wafer process



C. Marxer, N. F. de Rooij, J. MEMS 97

